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**Eun et al.**

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(54) **DISPLAY DEVICE INCLUDING STAGE TRANSISTOR**

G09G 2310/0286; G09G 2310/08; G09G 2320/0209; G09G 2320/0233; G09G 3/3225; G09G 2310/021; H10K 59/131

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See application file for complete search history.

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(57) **ABSTRACT**

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A display device is provided. The display device includes: a timing controlling unit generating an image data, a data control signal and a gate control signal; a data driving unit generating a data signal using the image data and the data control signal; a gate driving unit generating a gate1 signal, a new gate1 signal, an odd gate2 signal, an even gate2 signal and an emission signal using the gate control signal and including a plurality of stages; and a display panel displaying an image using the gate1 signal, the new gate1 signal, the odd gate2 signal, the even gate2 signal and the emission signal, wherein each of the plurality of stages includes: a gate1 signal block; an odd gate2 signal block; an even gate2 signal block; first and second stage transistors; and an emission signal block generating the emission signal. Accordingly, since the new gate signal is generated by using the stage transistor, the luminance deviation between the odd and even pixel lines is minimized.

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**G09G 3/3266** (2016.01)

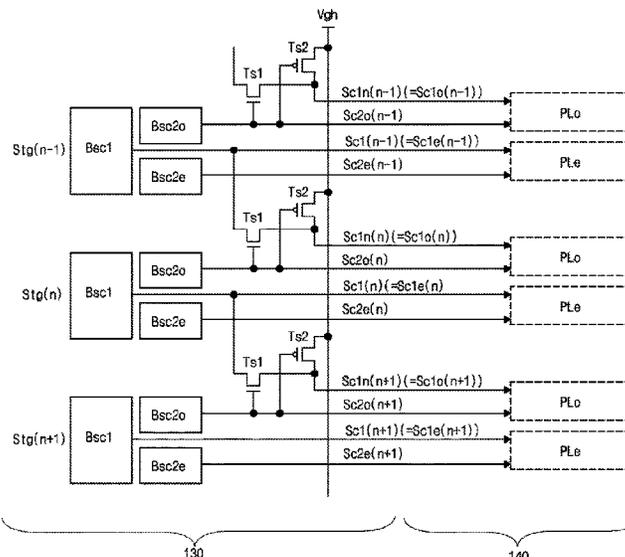
(52) **U.S. Cl.**

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**13 Claims, 10 Drawing Sheets**



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FIG. 1

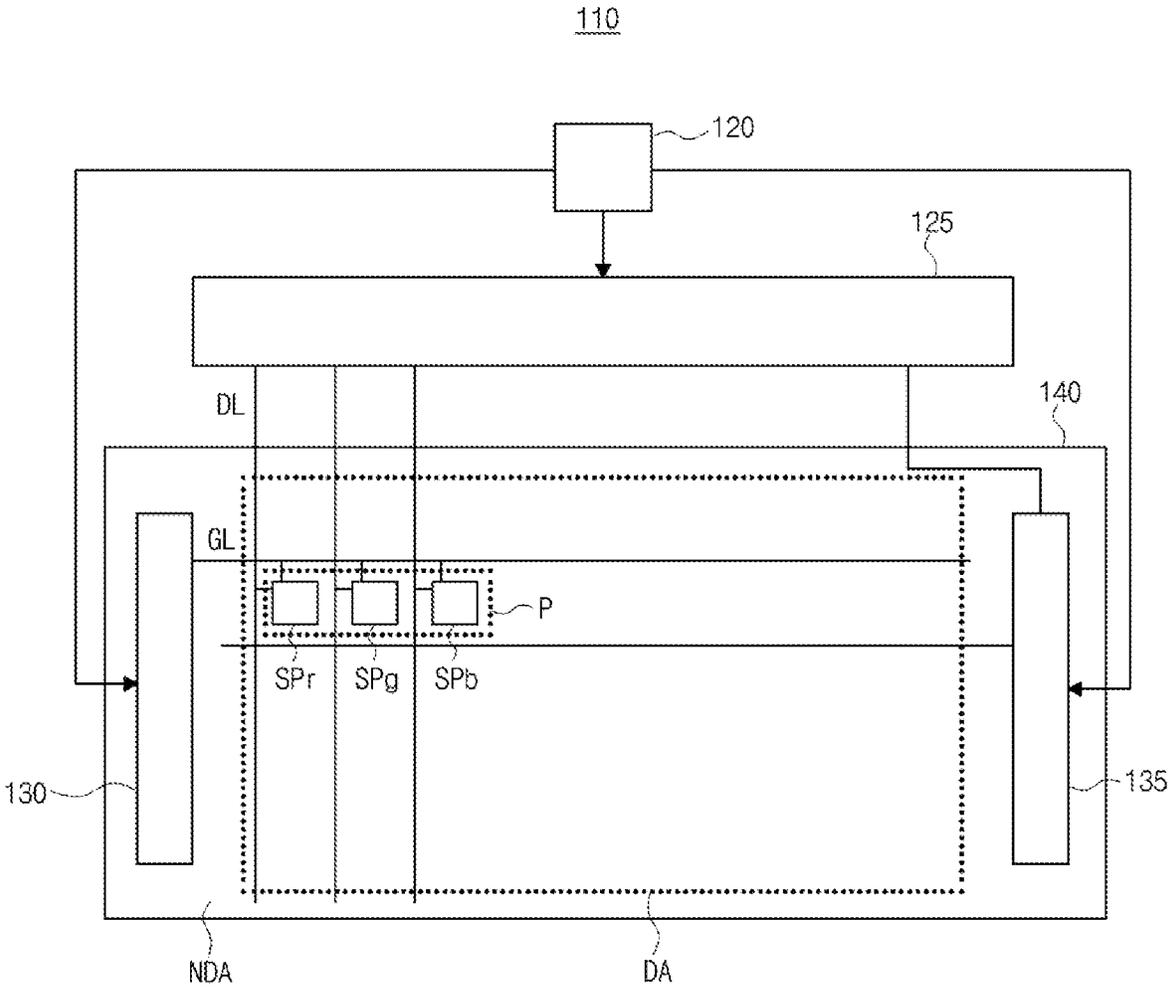


FIG. 2

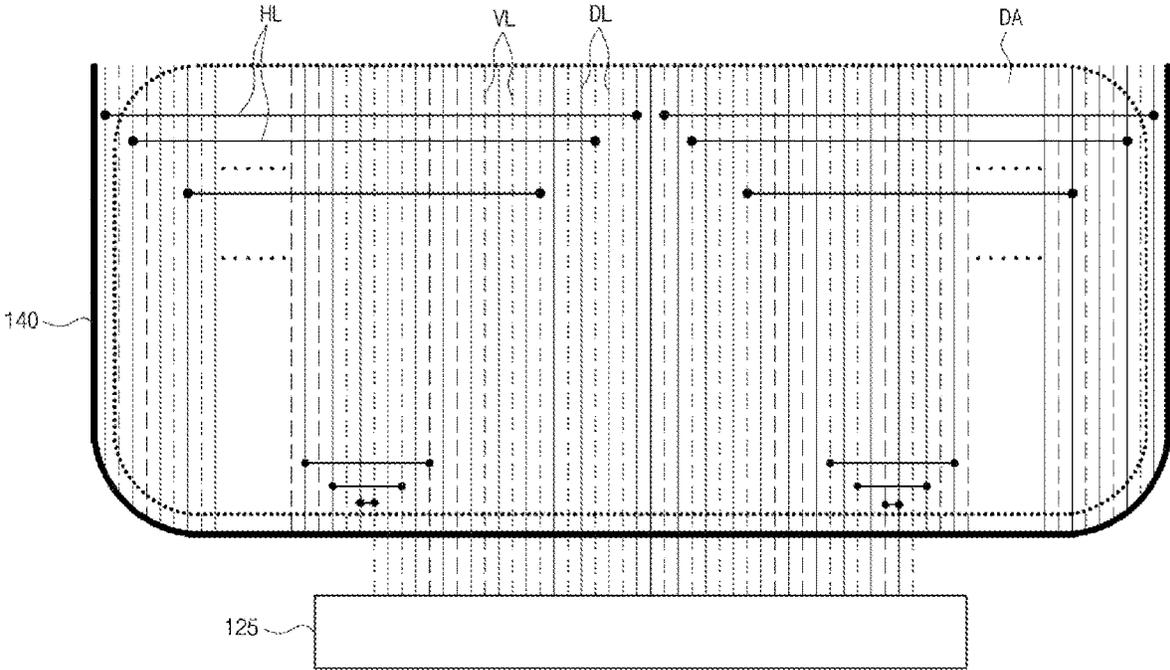


FIG. 3A

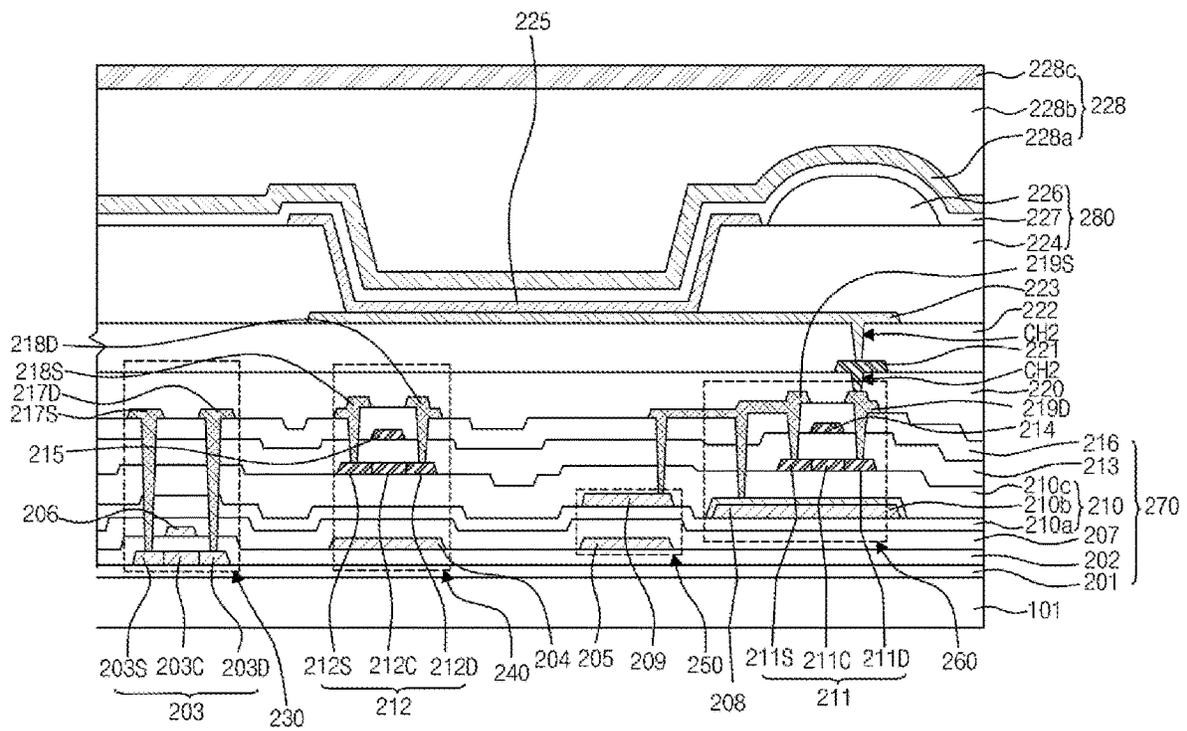


FIG. 3B

SPr, SPg, SPb

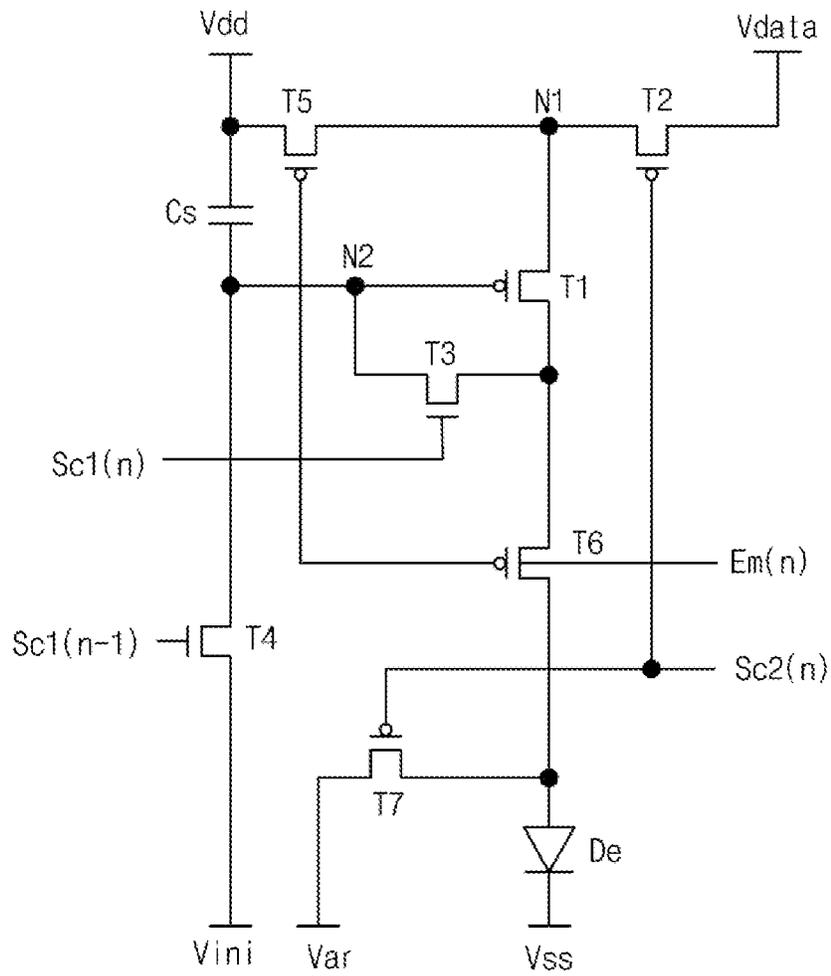


FIG. 4

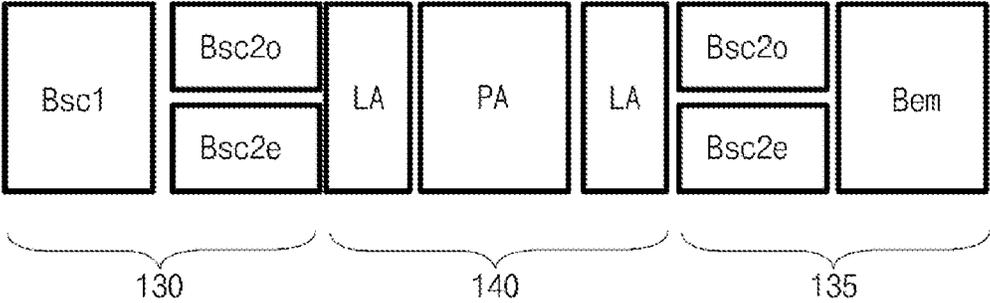


FIG. 5

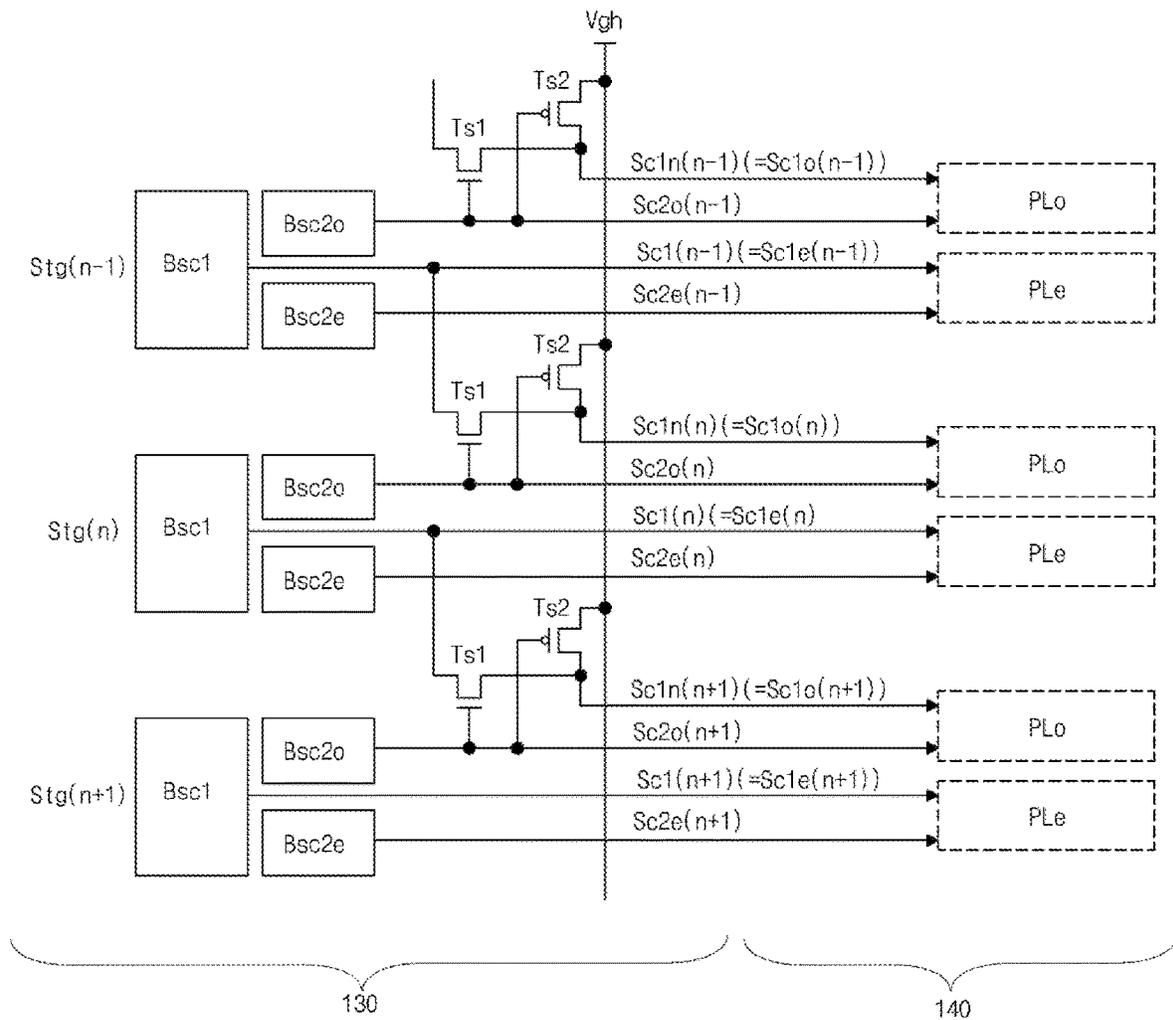


FIG. 6

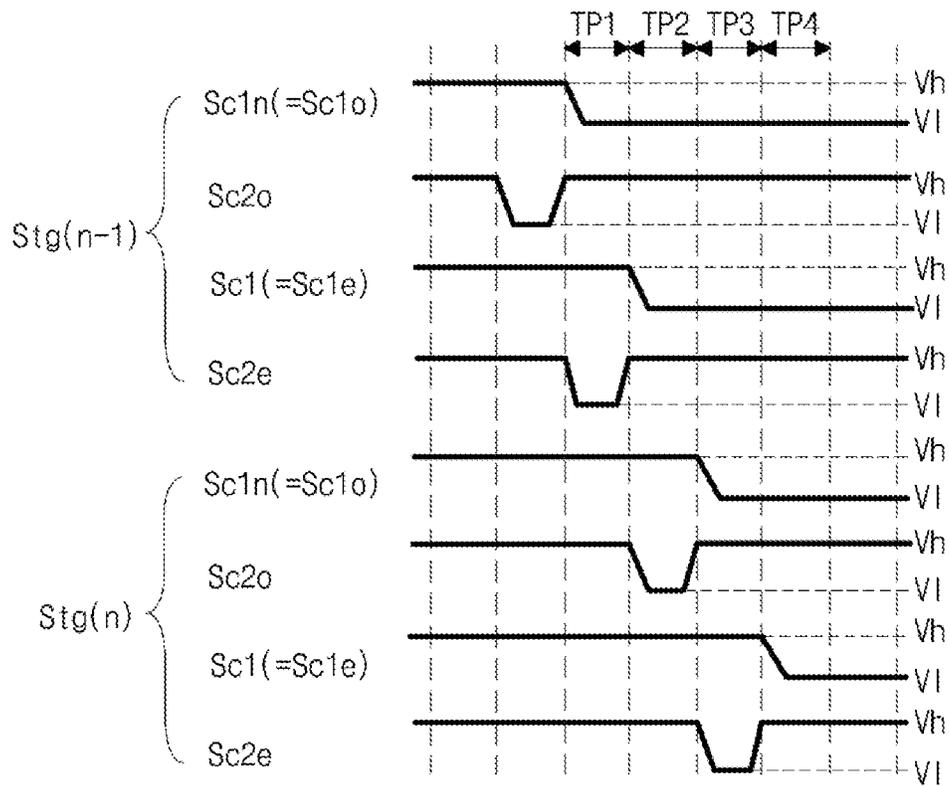


FIG. 7A

TP1

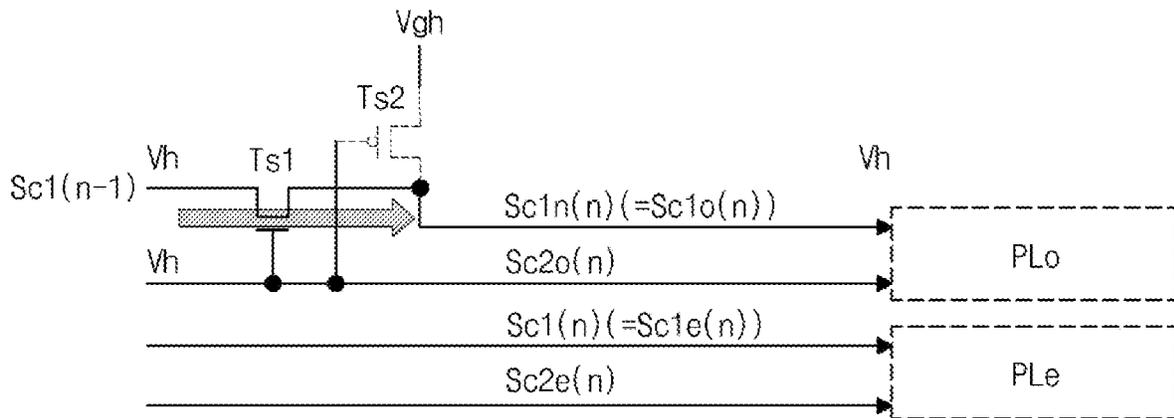


FIG. 7B

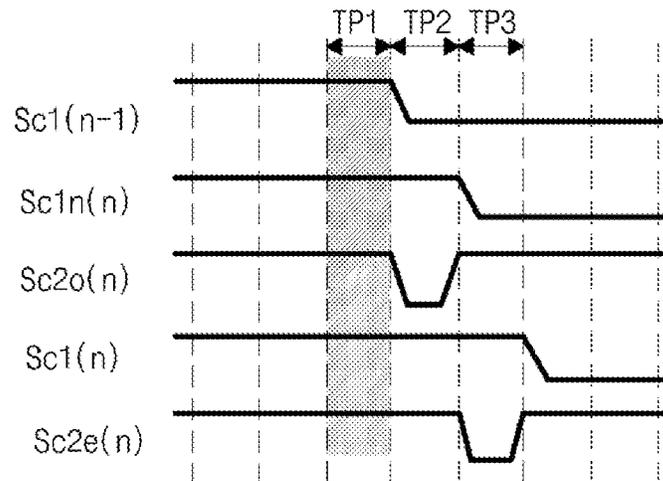


FIG. 8A

TP2

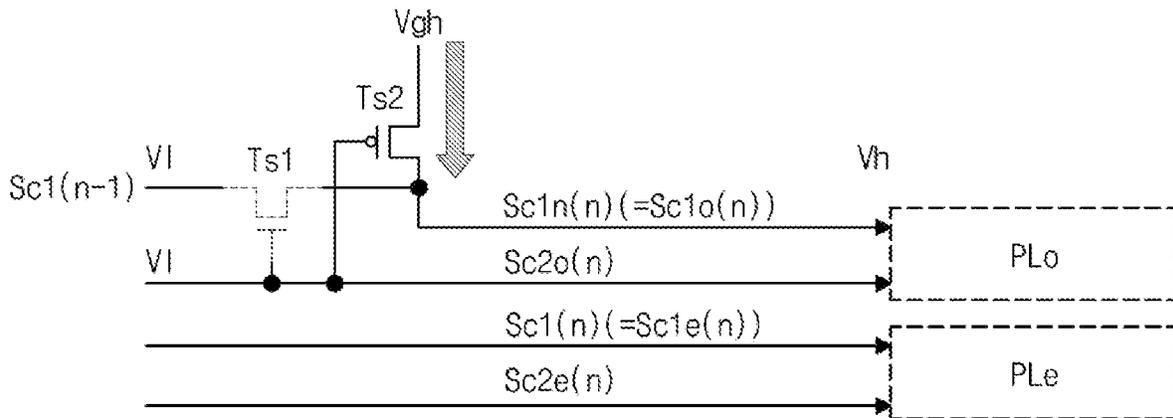


FIG. 8B

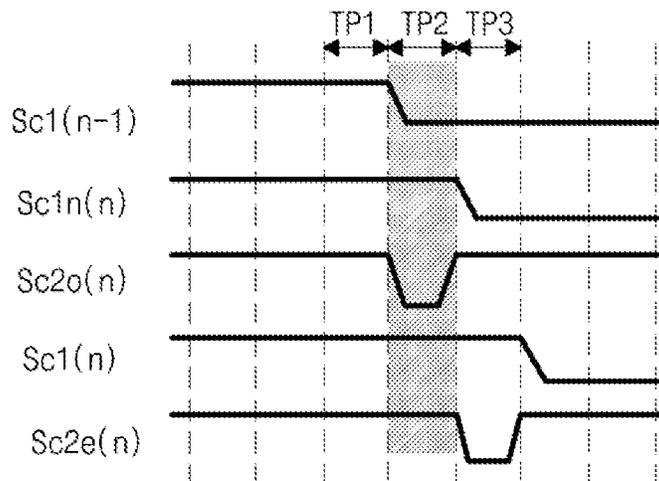


FIG. 9A

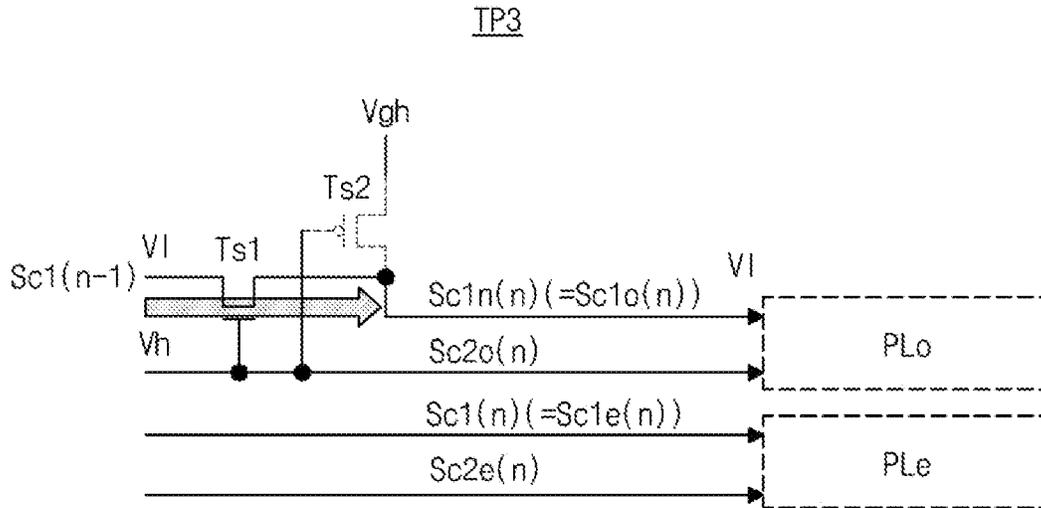
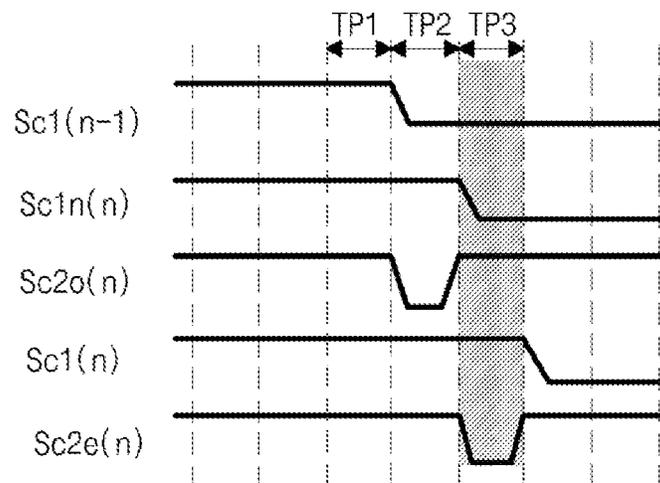


FIG. 9B



## DISPLAY DEVICE INCLUDING STAGE TRANSISTOR

### CROSS-REFERENCE TO RELATED APPLICATIONS

The present application claims the priority benefit of Korean Patent Application No. 10-2022-0182698, filed in Republic of Korea on Dec. 23, 2022, which is hereby incorporated by reference herein in its entirety into the present application.

### BACKGROUND

#### Technical Field

The present disclosure relates to a display device, and more particularly, to an organic light emitting diode display device generating a new gate signal using a stage transistor.

#### Discussion of the Related Art

Recently, with the advent of an information-oriented society, the interest in information displays for processing and displaying a massive amount of information and the demand for portable information media have increased. As such, a display field has rapidly advanced. Thus, various light and thin flat panel display devices have been developed and highlighted.

Among the various flat panel display devices, an organic light emitting diode (OLED) display device is an emissive type device that does not include a backlight unit used in a non-emissive type device such as a liquid crystal display (LCD) device. As a result, the OLED display device has advantages in a viewing angle, a contrast ratio and a power consumption to be applied to various fields.

Since the OLED display device uses a plurality of gate signals, the OLED display device may include a complicated gate driving unit. When some of the plurality of gate signals may be supplied to different pixel lines, a time delay of the gate signal is generated to cause a luminance deviation between the pixel lines.

### SUMMARY OF THE DISCLOSURE

Accordingly, the present disclosure is directed to a display device that substantially obviates one or more of the problems due to limitations and disadvantages of the related art.

An object of the present disclosure is to provide a display device where a luminance deviation between odd and even pixel lines is minimized by generating a new gate signal using a stage transistor and supplying the new gate signal to one of the odd and even pixel lines.

Another object of the present disclosure is to provide a display device where deterioration of display quality such as a vertical triangle crosstalk is minimized by generating a new gate signal using a stage transistor and supplying the new gate signal to one of odd and even pixel lines in a display panel having a link line in a display area.

Additional features and advantages of the disclosure will be set forth in the description which follows, and in part will be apparent from the description, or can be learned by practice of the disclosure. These and other advantages of the disclosure will be realized and attained by the structure particularly pointed out in the written description and claims hereof as well as the appended drawings.

To achieve these and other advantages and in accordance with the purpose of the present disclosure, as embodied and broadly described herein, a display device includes: a timing controlling unit generating an image data, a data control signal and a gate control signal; a data driving unit generating a data signal using the image data and the data control signal; a gate driving unit generating a gate1 signal, a new gate1 signal, an odd gate2 signal, an even gate2 signal and an emission signal using the gate control signal and including a plurality of stages; and a display panel displaying an image using the gate1 signal, the new gate1 signal, the odd gate2 signal, the even gate2 signal and the emission signal, wherein each of the plurality of stages includes: a gate1 signal block generating the gate1 signal; an odd gate2 signal block generating the odd gate2 signal; an even gate2 signal block generating the even gate2 signal; first and second stage transistors switched according to the odd gate2 signal to generate the new gate1 signal; and an emission signal block generating the emission signal.

It is to be understood that both the foregoing general description and the following detailed description are explanatory and are intended to provide further explanation of the disclosure as claimed.

### BRIEF DESCRIPTION OF THE DRAWINGS

The accompanying drawings, which are included to provide a further understanding of the disclosure and are incorporated in and constitute a part of this specification, illustrate embodiments of the disclosure and together with the description serve to explain the principles of the disclosure. In the drawings:

FIG. 1 is a view showing a display device according to an embodiment of the present disclosure;

FIG. 2 is a plan view showing a display panel of a display device according to an embodiment of the present disclosure;

FIG. 3A is a cross-sectional view showing a display panel of a display device according to an embodiment of the present disclosure;

FIG. 3B is a circuit diagram showing a subpixel of a display device according to an embodiment of the present disclosure;

FIG. 4 is a block diagram showing first and second gate driving units and a display panel of a display device according to an embodiment of the present disclosure;

FIG. 5 is a view showing a first gate driving unit of a display device according to an embodiment of the present disclosure;

FIG. 6 is a view showing a plurality of signals outputted from a first gate driving unit of a display device according to an embodiment of the present disclosure;

FIGS. 7A and 7B are views showing an operation state of first and second stage transistors of an nth stage and a state of a plurality of signals, respectively, during a first period of a display device according to an embodiment of the present disclosure;

FIGS. 8A and 8B are views showing an operation state of first and second stage transistors of an nth stage and a state of a plurality of signals, respectively, during a second period of a display device according to an embodiment of the present disclosure; and

FIGS. 9A and 9B are views showing an operation state of first and second stage transistors of an nth stage and a state

of a plurality of signals, respectively, during a third period of a display device according to an embodiment of the present disclosure.

### DETAILED DESCRIPTION OF THE EMBODIMENTS

Advantages and features of the present disclosure, and implementation methods thereof will be clarified through following example embodiments described with reference to the accompanying drawings. The present disclosure may, however, be embodied in different forms and should not be construed as limited to the example embodiments set forth herein. Rather, these example embodiments are provided so that this disclosure can be sufficiently thorough and complete to assist those skilled in the art to fully understand the scope of the present disclosure. Further, the present disclosure is only defined by scopes of claims.

Hereinafter, a display device including a stage transistor according to embodiments of the present disclosure will be described in detail with reference to the accompanying drawings.

FIG. 1 is a view showing a display device according to an embodiment of the present disclosure. The display device may be an organic light emitting diode (OLED) display device.

In FIG. 1, a display device **110** according to an embodiment of the present disclosure includes a timing controlling unit **120**, a data driving unit **125**, first and second gate driving units **130** and **135** and a display panel **140**.

The timing controlling unit **120** generates an image data, a data control signal and a gate control signal using an image signal and a plurality of timing signals including a data enable signal, a horizontal synchronization signal, a vertical synchronization signal and a clock signal transmitted from an external system such as a graphic card or a television system. The image data and the data control signal are transmitted to the data driving unit **125**, and the gate control signal is transmitted to the first and second gate driving units **130** and **135**.

The data driving unit **125** generates a data signal (a data voltage) *Vdata* (of FIG. 3B) using the data control signal and the image data transmitted from the timing controlling unit **120** and transmits the data signal to a data line *DL* of the display panel **140**.

The first and second gate driving units **130** and **135** generate a gate signal (a gate voltage) *Sc1* and *Sc2* (of FIG. 3B) and an emission signal (an emission voltage) *Em* (of FIG. 3B) using the gate control signal transmitted from the timing controlling unit **120** and applies the gate signal *Sc1* and *Sc2* and the emission signal *Em* to a gate line *GL* of the display panel **140**.

The first and second gate driving units **130** and **135** may be a gate in panel (GIP) type formed in a non-display area *NDA* of a substrate of the display panel **140** having the gate line *GL*, the data line *DL* and a pixel *P*.

The display panel **140** includes a display area *DA* at a central portion thereof and a non-display area *NDA* surrounding the display area *DA*. The display panel **140** displays an image using the gate signal *Sc1* and *Sc2*, the emission signal *Em* and the data signal *Vdata*. For displaying an image, the display panel **140** includes a plurality of pixels *P*, a plurality of gate lines *GL* and a plurality of data lines *DL* in the display area *DA*.

Each of the plurality of pixels *P* includes red, green and blue subpixels *SPr*, *SPg* and *SPb*, and the gate line *GL* and the data line *DL* cross each other to define the red, green and

blue subpixels *SPr*, *SPg* and *SPb*. Each of the red, green and blue subpixels *SPr*, *SPg* and *SPb* is connected to the gate line *GL* and the data line *DL*.

When the display device **110** is an OLED display device, each of the red, green and blue subpixels *SPr*, *SPg* and *SPb* may include a plurality of transistors such as a switching transistor, a driving transistor and a sensing transistor, a storage capacitor and a light emitting diode.

The display device **110** where a link line may be disposed in the display area for reducing a bezel will be illustrated with reference to a drawing.

FIG. 2 is a plan view showing a display panel of a display device according to an embodiment of the present disclosure.

In FIG. 2, the display panel **140** of the display device **110** includes a plurality of vertical link lines *VL* and a plurality of horizontal link lines *HL* disposed in the display area *DA* adjacent to the data driving unit **125**.

The plurality of vertical link lines *VL* are disposed to be parallel to the plurality of data lines *DL* and to be spaced apart from each other. The plurality of horizontal link lines *HL* are disposed to cross the plurality of data lines *DL* and to be spaced apart from each other.

Some of the plurality of data lines *DL* and some of the plurality of vertical link lines *VL* are connected to the data driving unit **125** to receive the data signal *Vdata*. The plurality of horizontal link lines *HL* connect the vertical link line *VL* connected to the data driving unit **125** and the data line *DL* not connected to the data driving unit **125** to supply the data signal.

A structure and an operation of the subpixel *SP* and the gate driving unit **130** and **135** of the display device **110** will be illustrated with reference to a drawing.

FIG. 3A is a cross-sectional view showing a display panel of a display device according to an embodiment of the present disclosure, FIG. 3B is a circuit diagram showing a subpixel of a display device according to an embodiment of the present disclosure, FIG. 4 is a block diagram showing first and second gate driving units and a display panel of a display device according to an embodiment of the present disclosure, FIG. 5 is a view showing a first gate driving unit of a display device according to an embodiment of the present disclosure, and FIG. 6 is a view showing a plurality of signals outputted from a first gate driving unit of a display device according to an embodiment of the present disclosure.

In FIG. 3A, the display panel **140** of the display device **110** according to an embodiment of the present disclosure includes one driving transistor **260**, two switching transistors **230** and **240** and one storage capacitor **250**.

A driving element **270** and an emitting element electrically connected to the driving element **270** are disposed in one of the subpixels *SPr*, *SPg* and *SPb* on a substrate **101**. The driving element **270** and the emitting element **280** are insulated from each other by planarizing layers **220** and **222**.

The driving element **270** may be an array part including the driving transistor **260**, the switching transistors **230** and **240** and the storage capacitor **250** and driving one of the subpixels *SPr*, *SPg* and *SPb*. The emitting element **280** may be an array part for emission including an anode **223**, a cathode **227** and an emitting layer **225** between the anode **223** and the cathode **227**. The driving element **270** may be a first array part, and the emitting element **280** may be a second array part. The embodiments of the present disclosure are not limited thereto.

Although one driving transistor **260**, two switching transistors **230** and **240** and one storage capacitor **250** are shown in the embodiment of FIG. 3A, it is not limited thereto.

The driving transistor **260** and the at least one switching transistor use an oxide semiconductor layer as an active layer. The oxide semiconductor layer formed of an oxide semiconductor material has an excellent effect of blocking a leakage current and has a relatively low fabrication cost as compared with a polycrystalline silicon layer. For example, the oxide semiconductor layer may include indium gallium zinc oxide (IGZO), zinc oxide (ZnO), tin oxide (SnO<sub>2</sub>), copper oxide (Cu<sub>2</sub>O), nickel oxide (NiO), indium tin zinc oxide (ITZO) and/or indium aluminum zinc oxide (IAZO). The embodiments of the present disclosure are not limited thereto. In the embodiment of the present disclosure, to reduce a power consumption and a fabrication cost, the driving transistor **260** and the at least one switching transistor may be fabricated using an oxide semiconductor layer.

A transistor using a polycrystalline semiconductor layer including a polycrystalline semiconductor material, for example, polycrystalline silicon (poly-Si) has a relatively high operation speed and a relatively excellent reliability. In the embodiment of FIG. 3A, one of the switching transistors may include a polycrystalline semiconductor layer and the others of the switching transistors may include an oxide semiconductor layer. The embodiments of the present disclosure are not limited thereto.

At least one of one driving transistor **260** and two switching transistors **230** and **240** is a positive (P) type transistor and the others of one driving transistor **260** and two switching transistors **230** and **240** are a negative (N) type transistor. For example, the driving transistor **260** may be a P type, and the transistor having an oxide semiconductor layer of two switching transistors **230** and **240** may be a N type. The embodiments of the present disclosure are not limited thereto.

The substrate **101** may have multiple layers where at least one organic layer and at least one inorganic layer are alternately laminated. For example, the substrate **101** may have an organic layer including an organic material such as polyimide and an inorganic layer including an inorganic material such as silicon oxide (SiOx) alternately laminated with each other. The embodiments of the present disclosure are not limited thereto.

A lower buffer layer **201** may be disposed on the substrate **101**. The lower buffer layer **201** may block a permeable substance such as moisture. The lower buffer layer **201** may have multiple layers of silicon oxide (SiOx). A second buffer layer may be further disposed on the lower buffer layer **201** for protection from moisture.

A first switching transistor **230** (one of second to seventh transistors T2 to T7 (of FIG. 3B)) may be disposed on the lower buffer layer **201**. The first switching transistor **230** may use a polycrystalline semiconductor layer as an active layer. The first switching transistor **230** may include a first active layer **203** having a channel where an electron or a hole moves, a first gate electrode **206**, a first source electrode **217S** and a first drain electrode **217D**.

The first active layer **203** may include a polycrystalline semiconductor material. The first active layer **203** may include a first channel region **203C** and a first source region **203S** and a first drain region **203D** at both sides of the first channel region **203C**.

The first source region **203S** and the first drain region **203D** may include a region conductorized by doping an intrinsic polycrystalline semiconductor pattern with an impurity of a V group or a III group, for example, phos-

phorus (P) or boron (B). The first channel region **203C** where the polycrystalline semiconductor material is kept as an intrinsic state may provide a moving path for an electron or a hole.

The first switching transistor **230** may include a first gate electrode **206** overlapping the first channel region **203C** of the first active layer **203**. A first gate insulating layer **202** may be disposed between the first gate electrode **206** and the first active layer **203**.

The first switching transistor **230** may have a top gate type where the first gate electrode **206** is disposed over the first active layer **203**. The embodiments of the present disclosure are not limited thereto. A first capacitor electrode **205** and a second light shielding layer **204** of the second switching transistor **240** may be formed of a material for the first gate electrode **206** through one mask process. As a result, a number of the mask processes may be reduced.

The first gate electrode **206** may include a metallic material. For example, the first gate electrode **206** may have a single layer or multiple layers of one of molybdenum (Mo), aluminum (Al), chromium (Cr), gold (Au), titanium (Ti), nickel (Ni), neodymium (Nd), copper (Cu) and an alloy thereof. It is not limited thereto.

A first interlayer insulating layer **207** may be disposed on the first gate electrode **206**. The first interlayer insulating layer **207** may include silicon nitride (SiNx). The first interlayer insulating layer **207** of silicon nitride (SiNx) may have a hydrogen particle. When heat treatment process is performed after the first active layer **203** is formed and the first interlayer insulating layer **207** is formed on the first active layer **203**, the hydrogen particles of the first interlayer insulating layer **207** penetrate into the first source region **203S** and the first drain region **203D** to improve and stabilize a conductivity of the polycrystalline semiconductor material. The above process may be referred to as a hydrogenation process.

The first switching transistor **230** may further include an upper buffer layer **210**, a second gate insulating layer **213** and a second interlayer insulating layer **216** sequentially on the first interlayer insulating layer **207**. The first switching transistor **230** may include a first source electrode **217S** and a first drain electrode **217D** disposed on the second interlayer insulating layer **216** and connected to the first source region **203S** and the first drain region **203D**, respectively.

The upper buffer layer **210** may separate the first active layer **203** including a polycrystalline semiconductor material from the second active layer **212** of the second switching transistor **240** including an oxide semiconductor material and the third active layer **211** of the driving transistor **260** including an oxide semiconductor material. The upper buffer layer **210** may provide a base for the second active layer **212** and the third active layer **211**.

A second interlayer insulating layer **216** may be disposed on the second gate electrode **215** of the second switching transistor **240** and the third gate electrode **214** of the driving transistor **260**. Since the second interlayer insulating layer **216** is disposed on the second active layer **212** and the third active layer **211** including an oxide semiconductor material, the second interlayer insulating layer **216** may include an inorganic material without a hydrogen particle.

The first source electrode **217S** and the first drain electrode **217D** may have a single layer or multiple layers of one of molybdenum (Mo), aluminum (Al), chromium (Cr), gold (Au), titanium (Ti), nickel (Ni), neodymium (Nd), copper (Cu) and an alloy thereof. It is not limited thereto.

The second switching transistor **240** (another of second to seventh transistors T2 to T7) may be disposed on the upper

buffer layer **210** and may include the second active layer **212** including an oxide semiconductor material, the second gate insulating layer **213** covering the second active layer **212**, the second gate electrode **215** on the second gate insulating layer **213**, the second interlayer insulating layer **216** covering the second gate electrode **215**, and the second source electrode **218S** and the second drain electrode **218D** on the second interlayer insulating layer **216**.

The second switching transistor **240** may further include a second light shielding layer **204** disposed under the upper buffer layer **210** and overlapping the second active layer **212**. The second light shielding layer **204** may include the same material as the first gate electrode **206** and may be disposed on the first gate insulating layer **202**.

The second light shielding layer **204** may be electrically connected to the second gate electrode **215** to constitute a dual gate. When the second switching transistor **240** has a dual gate structure, a current flow through a second channel region **212C** may be more accurately controlled. Further, since a display device is formed to have a smaller size, a display device of a relatively high resolution may be obtained.

The second active layer **212** may include an oxide semiconductor material and may have a second channel region **212C**, a second source region **212S** and a second drain region **212D**. The second channel region may have an intrinsic state not doped with an impurity, and the second source region **212S** and the second drain region **212D** may have a conductorization state doped with an impurity.

The second source electrode **218S** and the second drain electrode **218D** may have a single layer or multiple layers of one of molybdenum (Mo), aluminum (Al), chromium (Cr), gold (Au), titanium (Ti), nickel (Ni), neodymium (Nd), copper (Cu) and an alloy thereof. It is not limited thereto.

The second source electrode **218S**, the second drain electrode **218D**, the first source electrode **217S** and the first drain electrode **217D** may be simultaneously formed on the second interlayer insulating layer **216** with the same material. As a result, a number of the mask processes may be reduced.

The driving transistor **260** (a first transistor T1 (of FIG. 3B)) may be disposed on the upper buffer layer **210**.

The driving transistor **260** may include a third active layer **211** including an oxide semiconductor material, a second gate insulating layer **213** covering the third active layer **211**, a third gate electrode **214** disposed on the second gate insulating layer **213** and overlapping the third active layer **211**, and a third source electrode **219S** and a third drain electrode **219D** on the second interlayer insulating layer **216**.

The driving transistor **260** may further include a first light shielding layer **208** disposed in the upper buffer layer **210** and overlapping the third active layer **211**. The first light shielding layer **208** may be formed to be inserted (or accommodated) into the upper buffer layer **210**.

For a structure where the first light shielding layer **208** is disposed in the upper buffer layer **210**, the first light shielding layer **208** may be disposed on a first upper sub-buffer layer **210a** over the first interlayer insulating layer **207**. A second upper sub-buffer layer **210b** may be disposed on the first light shielding layer **208** to cover the first light shielding layer **208** completely, and a third upper sub-buffer layer **210c** may be disposed on the second upper sub-buffer layer **210b**. For example, the upper buffer layer **210** may have a structure where the first upper sub-buffer layer **210a**, the second upper sub-buffer layer **210b** and the third upper sub-buffer layer **210c** are sequentially laminated.

The first upper sub-buffer layer **210a** and the third upper sub-buffer layer **210c** may include silicon oxide (SiOx). When the first upper sub-buffer layer **210a** and the third upper sub-buffer layer **210c** include silicon oxide (SiOx) without a hydrogen particle, the first upper sub-buffer layer **210a** and the third upper sub-buffer layer **210c** may be provided as a base for the second switching transistor **240** and the driving transistor **260** using an oxide semiconductor material susceptible to a hydrogen particle as an active layer.

The second upper sub-buffer layer **210b** may include silicon nitride (SiNx) having an excellent capturing ability for a hydrogen particle. The second upper sub-buffer layer **210b** may surround a top surface and a side surface of the first light shielding layer **208** to seal the first light shielding layer **208** completely.

A hydrogen particle generated in a hydrogenation process of the first switching transistor **230** using a polycrystalline semiconductor material as an active layer may pass through the upper buffer layer **210** to deteriorate a reliability of an oxide semiconductor material on the upper buffer layer **210**. For example, when a hydrogen particle penetrates into an oxide semiconductor material, a transistor including an oxide semiconductor material may have different threshold voltages or may have different conductivities of a channel according to a position where the oxide semiconductor material is disposed.

Since silicon nitride (SiNx) has excellent capturing ability for a hydrogen particle, deterioration of a reliability of the driving transistor **260** due to a hydrogen particle penetrating into an oxide semiconductor material may be prevented.

The first light shielding layer **208** may include a metallic material such as titanium (Ti) having an excellent capturing ability for a hydrogen particle. For example, the first light shielding layer **208** may have a single layer of titanium (Ti), multiple layers of molybdenum (Mo) and titanium (Ti) or a single layer of an alloy of molybdenum (Mo) and titanium (Ti). In another embodiment, the first light shielding layer **208** may include another metallic material including titanium (Ti).

Titanium (Ti) may capture a hydrogen particle diffused in the upper buffer layer **210** to prevent a hydrogen particle from reaching the third active layer **211**. When the first light shielding layer **208** of the driving transistor **260** is formed of a metallic material such as titanium (Ti) having a capturing ability for a hydrogen particle and is surrounded by silicon nitride (SiNx) having a capturing ability for a hydrogen particle, a reliability of a pattern of an oxide semiconductor material against a hydrogen particle is obtained.

Differently from the first upper sub-buffer layer **210a**, the second upper sub-buffer layer **210b** including silicon nitride (SiNx) is not disposed in the entire display area. Instead, the second upper sub-buffer layer **210b** may be disposed on a portion of the first upper sub-buffer layer **210a** to selectively cover the first light shielding layer **208**. The second upper sub-buffer layer **210b** may include a material such as silicon nitride (SiNx) different from a material of the first upper sub-buffer layer **210a**. As a result, when the second upper sub-buffer layer **210b** is disposed in the entire display area, the second upper sub-buffer layer **210b** may be peeled off. To prevent the peeling, the second upper sub-buffer layer **210b** may be selectively disposed on a portion where the first light shielding layer **208** is disposed.

The first light shielding layer **208** and the second upper sub-buffer layer **210b** may be disposed directly under the third active layer **211** to overlap the third active layer **211**. The first light shielding layer **208** and the second upper

sub-buffer layer **210b** may have a size greater than a size of the third active layer **211** to completely overlap the third active layer **211**.

The third source electrode **219S** of the driving transistor **260** may be electrically connected to the first light shielding layer **208**.

The storage capacitor **250** (Cs (of FIG. 3B)) may store the data signal applied through the data line and may provide the data signal to the emitting element. The storage capacitor **250** may include two corresponding electrodes and a dielectric layer between the two electrodes. For example, the storage capacitor **250** may include a first capacitor electrode **205** having the same material and the same layer as the first gate electrode **206** and a second capacitor electrode **209** having the same material and the same layer as the first light shielding layer **208**. The first interlayer insulating layer **207** and the first upper sub-buffer layer **210a** may be disposed between the first capacitor electrode **205** and the second capacitor electrode **209**. The second capacitor electrode **209** of the storage capacitor **250** may be electrically connected to the third source electrode **219S**.

Although the storage capacitor **250** may be disposed at a side of the driving transistor **260**, it is not limited thereto. In another embodiment, the storage capacitor **250** may be disposed to be laminated with the driving transistor **260**. When the storage capacitor **250** is laminated with the driving transistor **260**, at least portion of the third source electrode **219S** connected to the second capacitor electrode **209** may be omitted. For example, a fourth gate electrode may be further disposed on the third gate electrode **214** of the driving transistor **260**. The third gate electrode **214** and the fourth gate electrode may be spaced apart from each other to constitute the storage capacitor **250**.

A first planarizing layer **220** and a second planarizing layer **222** may be disposed on the driving element **270** to planarize the driving element **270**. The first planarizing layer **220** and the second planarizing layer **222** may include an organic material such as polyimide and acrylic resin. However, it is not limited thereto.

The emitting element **280** is disposed on the second planarizing layer **222**. The emitting element **280** includes a first electrode **223** as an anode, a second electrode **227** as a cathode corresponding to the first electrode **223** and an emitting layer between the first electrode **223** and the second electrode **227**. The first electrode **223** may be disposed in each subpixel.

The emitting element **280** may be connected to the driving element **270** through a connecting electrode **221** on the first planarizing layer **220**. For example, the first electrode **223** of the emitting element **280** and the third drain electrode **219D** of the driving transistor **260** of the driving element **270** may be connected to each other through the connecting electrode **221**.

The first electrode **223** may contact the connecting electrode **221** exposed through a contact hole CH1 in the second planarizing layer **222**. The connecting electrode **221** may contact the third drain electrode **219D** exposed through a second contact hole CH2 in the first planarizing layer **220**.

The first electrode **223** may have multiple layers including a transparent conductive material and an opaque conductive material having a relatively high reflectance. For example, the first electrode **223** may have a single layer or multiple layers including a transparent conductive material having a relatively high work function such as indium tin oxide (ITO) or indium zinc oxide (IZO) and an opaque conductive material such as aluminum (Al), silver (Ag), copper (Cu), lead (Pb), molybdenum (Mo), titanium (Ti) and an alloy

thereof. The embodiments of the present disclosure are not limited thereto. For example, the first electrode **223** may have a structure where a transparent conductive layer, an opaque conductive layer and a transparent conductive layer are sequentially laminated or a structure where a transparent conductive layer and an opaque conductive layer are sequentially laminated. The embodiments of the present disclosure are not limited thereto.

The emitting layer **225** may include a hole assisting layer, an emitting material layer and an electron assisting layer sequentially on the first electrode **223** or an electron assisting layer, an emitting material layer and a hole assisting layer sequentially on the first electrode **223**. A bank layer **224** may expose the first electrode **223** of the subpixel and may be referred to as a pixel defining layer. The bank layer **224** may include an opaque material, for example, a black colored material to prevent an optical interference between the adjacent subpixels. For example, the bank layer **224** may include a light shielding material of at least one of a color pigment, an organic black and a carbon. The embodiments of the present disclosure are not limited thereto. A spacer **226** may be disposed on the bank layer **224**.

The second electrode **227** of a cathode is disposed on a top surface and a side surface of the emitting layer **225** to face the first electrode **223** with the emitting layer **225** interposed therebetween. The second electrode **227** may be disposed in the entire display area as one body. When the organic light emitting diode display device has a top emission type, the second electrode **227** may include a transparent conductive material such as indium tin oxide (ITO) or indium zinc oxide (IZO). The embodiments of the present disclosure are not limited thereto.

An encapsulating element **228** for preventing penetration of moisture may be further disposed on the second electrode **227**. The encapsulating element **228** may include a first inorganic encapsulating layer **228a**, a second organic encapsulating layer **228b** and a third inorganic encapsulating layer **228c** sequentially laminated.

The first inorganic encapsulating layer **228a** and the third inorganic encapsulating layer **228c** of the encapsulating element **228** may include an inorganic material such as silicon oxide (SiOx). The second organic encapsulating layer **228b** of the encapsulating element **228** may include an organic material such as acrylic resin, epoxy resin, phenolic resin, polyamide resin and polyimide resin. The embodiments of the present disclosure are not limited thereto.

In FIG. 3B, each of red, green and blue subpixels SP<sub>r</sub>, SP<sub>g</sub> and SP<sub>b</sub> (SP) of the display panel **140** of the display device **110** according to an embodiment of the present disclosure includes first to seventh transistors T1 to T7, a storage capacitor Cs and a light emitting diode De. At least one of the first to seventh transistors T1 to T7 may be an oxide semiconductor thin film transistor, and the others of the first to seventh transistors T1 to T7 may be low temperature polycrystalline silicon thin film transistor.

For example, the first, second, fifth, sixth and seventh transistors T1, T2, T5, T6 and T7 may be a positive (P) type low temperature polycrystalline silicon thin film transistor, and the third and fourth transistors T3 and T4 may be a negative (N) type oxide semiconductor thin film transistor.

Alternatively, the second, fifth, sixth and seventh transistors T2, T5, T6 and T7 may be a low temperature polycrystalline silicon thin film transistor, and the first, third and fourth transistors T1, T3 and T4 may be an oxide semiconductor thin film transistor.

The first transistor T1 of a driving transistor is switched according to a voltage of the first capacitor electrode **205** of

the storage capacitor Cs. A gate electrode of the first transistor T1 is connected to the first capacitor electrode 205 of the storage capacitor Cs, a drain electrode of the third transistor T3 and a drain electrode of the fourth transistor T4, a source electrode of the first transistor T1 is connected to a source electrode of the second transistor T2 and a drain electrode of the fifth transistor T5, and a drain electrode of the first transistor T1 is connected to a source electrode of the third transistor T3 and a source electrode of the sixth transistor T6.

The second transistor T2 of a switching transistor is switched according to an nth gate2 signal Sc2(n). A gate electrode of the second transistor T2 is connected to the nth gate2 signal Sc2(n), a source electrode of the second transistor T2 is connected to a source electrode of the first transistor T1 and a drain electrode of the fifth transistor T5, and a drain electrode of the second transistor T2 is connected to the data signal Vdata.

The third transistor T3 of a sensing transistor is switched according to an nth gate1 signal Sc1(n). A gate electrode of the third transistor T3 is connected to the nth gate1 signal Sc1(n), a source electrode of the third transistor T3 is connected to a drain electrode of the first transistor T1 and a source electrode of the sixth transistor T6, and a drain electrode of the third transistor T3 is connected to a gate electrode of the first transistor T1, a first capacitor electrode 205 of the storage capacitor Cs and a drain electrode of the fourth transistor T4.

The fourth transistor T4 is switched according to an (n-1)th gate1 signal Sc1(n-1). A gate electrode of the fourth transistor T4 is connected to the (n-1)th gate1 signal Sc1(n-1), a source electrode of the fourth transistor T4 is connected to an initial voltage Vini, and a drain electrode of the fourth transistor T4 is connected to a gate electrode of the first transistor T1, a first capacitor electrode 205 of the storage capacitor Cs and a drain electrode of the third transistor T3.

The fifth transistor T5 is switched according to an nth emission signal Em(n). A gate electrode of the fifth transistor T5 is connected to the nth emission signal Em(n), a source electrode of the fifth transistor T5 is connected to a high level voltage Vdd and the second capacitor electrode 209 of the storage capacitor Cs, and a drain electrode of the fifth transistor T5 is connected to a source electrode of the first transistor T1 and a source electrode of the second transistor T2.

The sixth transistor T6 of an emission transistor is switched according to an nth emission signal Em(n). A gate electrode of the sixth transistor T6 is connected to the nth emission signal Em(n), a source electrode of the sixth transistor T6 is connected to a drain electrode of the first transistor T1 and a source electrode of the third transistor T3, and a drain electrode of the sixth transistor T6 is connected to an anode of the light emitting diode De and a source electrode of the seventh transistor T7.

The seventh transistor T7 is switched according to an nth gate2 signal Sc2(n). A gate electrode of the seventh transistor T7 is connected to the nth gate2 signal Sc2(n), a source electrode of the seventh transistor T7 is connected to a drain electrode of the sixth transistor T6 and an anode of the light emitting diode De, and a drain electrode of the seventh transistor T7 is connected to an anode reset voltage Var.

The storage capacitor Cs stores the data signal Vdata and the threshold voltage Vth. A first capacitor electrode of the storage capacitor Cs is connected to the gate electrode of the first transistor T1 and the drain electrode of the fourth

transistor T4, and a second capacitor electrode of the storage capacitor Cs is connected to the source electrode of the fifth transistor T5.

The light emitting diode De is connected between the sixth and seventh transistors T6 and T7 and the low level voltage Vss to emit light of a luminance proportional to a current of the first transistor T1. An anode of the light emitting diode De is connected to the drain electrode of the sixth transistor T6 and the source electrode of the seventh transistor T7, and a cathode of the light emitting diode De is connected to the low level voltage Vss.

The source electrode of the first transistor T1, the source electrode of the second transistor T2 and the drain electrode of the fifth transistor T5 constitute a first node N1, and the gate electrode of the first transistor T1, the drain electrode of the third transistor T3, the first capacitor electrode of the storage capacitor Cs and the drain electrode of the fourth transistor T4 constitute a second node N2.

In FIG. 4, the first gate driving unit 130 of the display device 110 according to an embodiment of the present disclosure includes a gate1 signal block Bsc1, an odd gate2 signal block Bsc2o and an even gate2 signal block Bsc2e, and the second gate driving unit 135 of the display device 110 according to an embodiment of the present disclosure includes an emission signal block Bem, an odd gate2 signal block Bsc2o and an even gate2 signal block Bsc2e. The display panel 140 includes a pixel area PA and a link area LA.

The gate1 signal block Bsc1, the odd gate2 signal block Bsc2o and the even gate2 signal block Bsc2e at one side of the pixel area PA may be one stage of a shift register, and the emission signal block Bem, the odd gate2 signal block Bsc2o and the even gate2 signal block Bsc2e at an opposite side of the pixel area PA may be one stage of a shift register. The shift register may include a plurality of stages connected to each other by a cascade type.

In the first gate driving unit 130, the gate1 signal block Bsc1 generates a gate1 signal Sc1, the odd gate2 signal block Bsc2o generates a gate2 signal Sc2, and the even gate2 signal block Bsc2e generates the gate2 signal Sc2.

The gate1 signal Sc1 of the gate1 signal block Bsc1 is supplied to an even pixel line PLe (of FIG. 5) of the pixel area PA through the link area LA. The gate2 signal Sc2 of the odd gate2 signal block Bsc2o is supplied to an odd pixel line PLo (of FIG. 5) through the link area LA, and the gate2 signal Sc2 of the even gate2 signal block Bsc2e is supplied to the even pixel line PLe of the pixel area PA through the link line LA.

The even pixel line PLe may be a row of pixels arranged in even order from a top portion of the display panel 140, and the odd pixel line PLo may be a row of pixels arranged in odd order from the top portion of the display panel 140.

First and second stage transistors Ts1 and Ts2 (of FIG. 5) are disposed in the odd and even gate2 signal blocks Bsc2o and Bsc2e or the link area LA. The first and second stage transistors Ts1 and Ts2 generate a new gate1 signal Sc1n (of FIG. 5) using the odd gate2 signal Sc2o, the gate1 signal Sc1 of a previous stage and a gate high voltage Vgh (of FIG. 5), and the new gate1 signal Sc1n is supplied to the odd pixel line PLo of the pixel area PA through the link area LA.

In another embodiment, the first and second gate driving units 130 and 135 may be symmetrically constituted with respect to each other. For example, each of the first and second gate driving units 130 and 135 may include the gate1 signal block Bsc1, the odd gate2 signal block Bsc2o, the even gate2 signal block Bsc2e and the emission block Bem.

In FIG. 5, the gate1 signal block Bsc1 of an nth stage Stg(n) of the first gate driving unit 130 generates an nth gate1 signal Sc1(n) and supplies the nth gate1 signal Sc1(n) to the even pixel line PLe as an nth even gate1 signal Sc1e(n). The odd gate2 signal block Bsc2o of the nth stage Stg(n) of the first gate driving unit 130 generates an nth odd gate2 signal Sc2o(n) and supplies the nth odd gate2 signal Sc2o(n) to the odd pixel line PLo. The even gate2 signal block Bsc2e of the nth stage Stg(n) of the first gate driving unit 130 generates an nth even gate2 signal Sc2e(n) and supplies the nth even gate2 signal Sc2e(n) to the even pixel line PLe.

The first and second stage transistors Ts1 and Ts2 are disposed between an output terminal of the nth stage Stg(n) and the odd and even pixel lines PLo and PLe. The first and second stage transistors Ts1 and Ts2 of the nth stage Stg(n) generates an nth new gate1 signal Sc1n(n) using an (n-1)th gate1 signal Sc1(n-1) of an (n-1)th stage Stg(n-1) of a previous stage and the gate high voltage Vgh and supplies the nth new gate1 signal Sc1n(n) to the odd pixel line PLo as an nth odd gate1 signal Sc1o(n).

For example, the first stage transistor Ts1 may be a negative (N) type thin film transistor having a width of about 50  $\mu\text{m}$  and a length of about 10  $\mu\text{m}$  ( $W/L=50\ \mu\text{m}/10\ \mu\text{m}=5$ ), and the second stage transistor Ts2 may be a positive (P) type thin film transistor having a width of about 10  $\mu\text{m}$  and a length of about 10  $\mu\text{m}$  ( $W/L=10\ \mu\text{m}/10\ \mu\text{m}=1$ ).

The first stage transistor Ts1 is switched according to the nth odd gate2 signal Sc2o(n) to transmit the (n-1)th gate1 signal Sc1(n-1), and the second stage transistor Ts2 is switched according to the nth odd gate2 signal Sc2o(n) to transmit the gate high voltage Vgh.

A gate electrode of the first stage transistor Ts1 is connected to the nth odd gate2 signal Sc2o(n), a source electrode of the first stage transistor Ts1 is connected to the (n-1)th gate1 signal Sc1(n-1), and a drain electrode of the first stage transistor Ts1 is connected to the odd pixel line PLo.

A gate electrode of the second stage transistor Ts2 is connected to the nth odd gate2 signal Sc2o(n), a source electrode of the second stage transistor Ts2 is connected to the gate high voltage Vgh, and a drain electrode of the second stage transistor Ts2 is connected to the odd pixel line PLo.

Similarly, the gate1 signal block Bsc1 of an (n+1)th stage Stg(n+1) of the first gate driving unit 130 generates an (n+1)th gate1 signal Sc1(n+1) and supplies the (n+1)th gate1 signal Sc1(n+1) to the even pixel line PLe as an (n+1)th even gate1 signal Sc1e(n+1). The odd gate2 signal block Bsc2o of the (n+1)th stage Stg(n+1) of the first gate driving unit 130 generates an (n+1)th odd gate2 signal Sc2o(n+1) and supplies the (n+1)th odd gate2 signal Sc2o(n+1) to the odd pixel line PLo. The even gate2 signal block Bsc2e of the (n+1)th stage Stg(n+1) of the first gate driving unit 130 generates an (n+1)th even gate2 signal Sc2e(n+1) and supplies the (n+1)th even gate2 signal Sc2e(n+1) to the even pixel line PLe.

The first and second stage transistors Ts1 and Ts2 of the (n+1)th stage Stg(n+1) generates an (n+1)th new gate1 signal Sc1n(n+1) using the nth gate1 signal Sc1(n) of an nth stage Stg(n) of a previous stage and the gate high voltage Vgh and supplies the (n+1)th new gate1 signal Sc1n(n+1) to the odd pixel line PLo as an (n+1)th odd gate1 signal Sc1o(n+1).

For example, the gate high voltage may be a logic high voltage Vh.

In another embodiment, the first and second stage transistors Ts1 and Ts2 may be disposed in the first gate driving

unit 130 or in the link area LA of the display panel 140. However, it is not limited thereto.

In FIG. 6, the new gate1 signal Sc1n (i.e., the odd gate1 signal Sc1o) of the (n-1)th stage Stg(n-1) of the first gate driving unit 130 has a logic low voltage V<sub>l</sub> during first, second, third and fourth periods TP1, TP2, TP3 and TP4, and the odd gate2 signal Sc2o of the (n-1)th stage Stg(n-1) of the first gate driving unit 130 has a logic high voltage V<sub>h</sub> during the first, second, third and fourth periods TP1, TP2, TP3 and TP4. The gate1 signal Sc1 (i.e., the even gate1 signal Sc1e) of the (n-1)th stage Stg(n-1) of the first gate driving unit 130 has a logic high voltage V<sub>h</sub> during the first period TP1 and has a logic low voltage V<sub>l</sub> during the second, third and fourth periods TP2, TP3 and TP4. The even gate2 signal Sc2e of the (n-1)th stage Stg(n-1) of the first gate driving unit 130 has a logic low voltage V<sub>l</sub> during the first period TP1 and has a logic high voltage V<sub>h</sub> during the second, third and fourth periods TP2, TP3 and TP4.

The new gate1 signal Sc1n (i.e., the odd gate1 signal Sc1o) of the nth stage Stg(n) of the first gate driving unit 130 has a logic high voltage V<sub>h</sub> during the first and second periods TP1 and TP2 and has a logic low voltage V<sub>l</sub> during the third and fourth periods TP3 and TP4. The odd gate2 signal Sc2o of the nth stage Stg(n) of the first gate driving unit 130 has a logic high voltage V<sub>h</sub> during the first, third and fourth periods TP1, TP3 and TP4 and has a logic high voltage V<sub>h</sub> during the second period TP2. The gate1 signal Sc1 (i.e., the even gate1 signal Sc1e) of the nth stage Stg(n) of the first gate driving unit 130 has a logic high voltage V<sub>h</sub> during the first, second and third periods TP1, TP2 and TP3 and has a logic low voltage V<sub>l</sub> during the fourth period TP4. The even gate2 signal Sc2e of the nth stage Stg(n) of the first gate driving unit 130 has a logic high voltage V<sub>h</sub> during the first, second and fourth periods TP1, TP2 and TP4 and has a logic low voltage V<sub>l</sub> during the third period TP3.

During the first period TP1, in each of the odd and even pixel lines PLo and PLe, the second and seventh transistors T2 and T7 are turned off and the third and fourth transistors T3 and T4 are turned on. As a result, the initial voltage V<sub>ini</sub> is applied to the gate electrode and the drain electrode of the first transistor T1.

During the second period TP2, in the odd pixel line PLo, the fourth transistor T4 is turned off and the second, third and seventh transistors T2, T3 and T7 are turned on. As a result, the data signal V<sub>data</sub> is applied to the source electrode of the first transistor T1, and the threshold voltage V<sub>th</sub> of the first transistor T1 is stored in the storage capacitor C<sub>s</sub> (sampling). Further, the anode reset voltage V<sub>ar</sub> is applied to the anode of the light emitting diode De. During the second period TP2, in the even pixel line PLe, the second and seventh transistors T2 and T7 are turned off and the third and fourth transistors T3 and T4 are turned on. As a result, voltages of the gate electrode and the drain electrode of the first transistor T1 are kept as the initial voltage V<sub>ini</sub>.

During the third period TP3, in the odd pixel line PLo, the second, third, fourth and seventh transistors T2, T3, T4 and T7 are turned off. As a result, voltages of the gate electrode, the source electrode and the drain electrode of the first transistor T1 are maintained. During the third period TP3, in the even pixel line PLe, the fourth transistor T4 is turned off and the second, third and seventh transistors T2, T3 and T7 are turned on. As a result, the data signal V<sub>data</sub> is applied to the source electrode of the first transistor T1, and the threshold voltage V<sub>th</sub> of the first transistor T1 is stored in the storage capacitor C<sub>s</sub> (sampling). Further, the anode reset voltage V<sub>ar</sub> is applied to the anode of the light emitting diode De.

During the fourth period TP4, in each of the odd and even pixel lines PLo and PLe, the second, third, fourth and seventh transistors T2, T3, T4 and T7 are turned off. As a result, voltages of the gate electrode, the source electrode and the drain electrode of the first transistor T1 are maintained.

When the odd and even pixel lines PLo and PLe perform a sampling for the threshold voltage Vth of the first transistor T1 using one gate1 signal Sc1, a rising timing of the even gate2 signal Sc2e may coincide with a falling timing of the gate1 signal Sc1 and a time delay may not occur in the even pixel line PLe. However, a time delay between a rising timing of the odd gate2 signal Sc2o and a falling timing of the gate1 signal Sc1 may occur in the odd pixel line PLo. As a result, a coupling between a vertical link line VL where the data signal Vdata is applied and the first node N1 may occur for the delayed time, and a voltage of the second node N2 may increase. Accordingly, luminance deviation between the odd and even pixel lines PLo and PLe may occur, and deterioration of a display quality such as a vertical triangle crosstalk may occur.

However, in the display device 110 according to an embodiment of the present disclosure, the odd and even pixel lines PLo and PLe perform a sampling for the threshold voltage Vth of the first transistor T1 using the odd and even gate1 signals Sc1o and Sc1e, respectively. As a result, in the odd pixel line PLo, a rising timing of the odd gate2 signal Sc2o coincides with a falling timing of the odd gate1 signal Sc1o and a time delay does not occur. Further, in the even pixel line PLe, a rising timing of the even gate2 signal Sc2e coincides with a falling timing of the even gate1 signal Sc1e and a time delay does not occur.

Accordingly, a voltage rising of the second node N2 due to a coupling between the vertical link line VL where the data voltage Vdata is applied and the first node N1 is prevented, the luminance deviation between the odd and even pixel lines PLo and PLe is minimized, and deterioration of the display quality such as a vertical triangle crosstalk is prevented.

An operation of generating the new gate1 signal Sc1n due to the first and second stage transistors Ts1 and Ts2 may be illustrated with reference to drawings.

FIGS. 7A and 7B are views showing an operation state of first and second stage transistors of an nth stage and a state of a plurality of signals, respectively, during a first period of a display device according to an embodiment of the present disclosure, FIGS. 8A and 8B are views showing an operation state of first and second stage transistors of an nth stage and a state of a plurality of signals, respectively, during a second period of a display device according to an embodiment of the present disclosure, and FIGS. 9A and 9B are views showing an operation state of first and second stage transistors of an nth stage and a state of a plurality of signals, respectively, during a third period of a display device according to an embodiment of the present disclosure.

In FIGS. 7A and 7B, during the first period TP1, the (n-1)th gate1 signal Sc1(n-1), the nth odd gate2 signal Sc2o(n), the nth gate1 signal Sc1(n) and the nth even gate2 signal Sc2e(n) have a logic high voltage Vh.

As a result, in the nth stage Stg(n), the first stage transistor Ts1 is turned on and the second stage transistor Ts2 is turned off, and the nth new gate1 signal Sc1n(n) has a logic high voltage Vh due to the (n-1)th gate1 signal Sc1(n-1).

In FIGS. 8A and 8B, during the second period TP2, the (n-1)th gate1 signal Sc1(n-1) and the nth odd gate2 signal

Sc2o(n) have a logic low voltage, and the nth gate1 signal Sc1(n) and the nth even gate2 signal Sc2e(n) have a logic high voltage Vh.

As a result, in the nth stage Stg(n), the first stage transistor Ts1 is turned off and the second stage transistor Ts2 is turned on, and the nth new gate1 signal Sc1n(n) has a logic high voltage Vh due to the gate high voltage Vgh.

In FIGS. 9A and 9B, during the third period TP3, the (n-1)th gate1 signal Sc1(n-1) and the nth even gate2 signal Sc2e(n) have a logic low voltage Vl, and the nth gate1 signal Sc1(n) and the nth odd gate2 signal Sc2o(n) have a logic high voltage Vh.

As a result, in the nth stage Stg(n), the first stage transistor Ts1 is turned on and the second stage transistor Ts2 is turned off, and the nth new gate1 signal Sc1n(n) has a logic low voltage Vl due to the (n-1)th gate1 signal Sc1(n-1).

The first and second stage transistors Ts1 and Ts2 of the nth stage Stg(n) are switched according to the nth odd gate2 signal Sc2o(n) to generate the nth new gate1 signal Sc1n(n) using the (n-1)th gate1 signal Sc1(n-1) of the (n-1)th stage Stg(n-1) as a previous stage or the gate high voltage Vgh and to supply the nth new gate1 signal Sc1n(n) to the odd pixel line PLo as the nth odd gate1 signal Sc1o(n).

In the display device 110 according to an embodiment of the present disclosure, the first and second stage transistors Ts1 and Ts2 are disposed between the output terminal of the first gate driving unit 130 and the odd and even pixel lines PLo and PLe, the first and second stage transistors Ts1 and Ts2 generates the new gate1 signal Sc1n using the gate1 signal Sc1 of the previous stage and the gate high voltage Vgh, and the new gate1 signal Sc1n is supplied to the odd pixel line PLo as the odd gate1 signal Sc1o.

Since the odd and even pixel lines PLo and PLe perform a sampling for the threshold voltage Vth of the first transistor T1 using the odd and even gate1 signals Sc1o and Sc1e, respectively, the rising timing of the gate2 signal Sc2 coincides with the falling timing of the gate1 signal Sc1 in the odd and even pixel lines PLo and PLe. As a result, the voltage rising of the second node N2 due to the coupling between the vertical link line VL where the data signal Vdata is applied and the first node N1 is prevented, the luminance deviation between the odd and even pixel lines PLo and PLe is minimized, and deterioration of the display quality such as a vertical triangle crosstalk is prevented.

Consequently, in the display device 110 according to an embodiment of the present disclosure, since the new gate signal generated by using the stage transistor is supplied to one of the odd and even pixel lines, the luminance deviation between the odd and even pixel lines is minimized.

Further, since the new gate signal is generated by using the stage transistor in the display panel where the link line is disposed in the display area and is supplied to one of the odd and even pixel lines, deterioration of the display quality such as a vertical triangle crosstalk is minimized.

It will be apparent to those skilled in the art that various modifications and variation can be made in the present disclosure without departing from the scope of the disclosure. Thus, it is intended that the present disclosure cover the modifications and variations of this disclosure provided they come within the scope of the appended claims.

What is claimed is:

1. A display device, comprising:

- a timing controller configured to generate an image data,
- a data control signal and a gate control signal;
- a data driver configured to generate a data signal using the image data and the data control signal;

17

a gate driver configured to generate an even gate1 signal, an odd gate1 signal, an odd gate2 signal, an even gate2 signal and an emission signal using the gate control signal and including a plurality of stages; and  
 a display panel configured to generate an image using the even gate1 signal, the odd gate1 signal, the odd gate2 signal, the even gate2 signal and the emission signal, wherein each of the plurality of stages comprises:  
 a gate1 signal circuit configured to generate the even gate1 signal;  
 an odd gate2 signal circuit configured to generate the odd gate2 signal;  
 an even gate2 signal circuit configured to generate the even gate2 signal;  
 first and second stage transistors switched according to the odd gate2 signal to generate the odd gate1 signal; and  
 an emission signal circuit configured to generate the emission signal,  
 wherein the display panel includes an odd pixel line and an even pixel line,  
 wherein the odd gate1 signal outputted from the first and second stage transistors and the odd gate2 signal outputted from the odd gate2 signal circuit are supplied to the odd pixel line of the display panel, and  
 wherein the even gate1 signal outputted from the gate1 signal circuit and the even gate2 signal outputted from the even gate2 signal circuit are supplied to the even pixel line of the display panel.

2. The display device of claim 1, wherein the plurality of stages include an (n-1)th stage and an nth stage,  
 wherein a gate electrode, a source electrode and a drain electrode of the first stage transistor of the nth stage are connected to the odd gate2 signal circuit of the nth stage, the gate1 signal circuit of the (n-1)th stage and the display panel, respectively, and  
 wherein a gate electrode, a source electrode and a drain electrode of the second stage transistor of the nth stage are connected to the odd gate2 signal circuit of the nth stage, a first logic voltage and the display panel, respectively.

3. The display device of claim 2, wherein, in the (n-1)th stage, the odd gate1 signal has a second logic voltage lower than the first logic voltage during first, second, third and fourth periods, the odd gate2 signal has the first logic voltage during the first, second, third and fourth periods, the even gate1 signal has the first logic voltage during the first period and has the second logic voltage during the second, third and fourth periods, and the even gate2 signal has the second logic voltage during the first period and has the first logic voltage during the second, third and fourth periods, and

wherein, in the nth stage, the odd gate1 signal has the first logic voltage during the first and second periods and has the second logic voltage during the third and fourth periods, the odd gate2 signal has the first logic voltage during the first, third and fourth periods and has the second logic voltage during the second period, the even gate1 signal has the first logic voltage during the first, second and third periods and has the second logic voltage during the fourth period, and the even gate2 signal has the first logic voltage during the first, second and fourth periods and has the second logic voltage during the third period.

4. The display device of claim 3, wherein, during the first period, the first stage transistor of the nth stage is turned on and the second stage transistor of the nth stage is turned off

18

such that the even gate1 signal of the nth stage has the first logic voltage due to the even gate1 signal of the (n-1)th stage,

wherein, during the second period, the first stage transistor of the nth stage is turned off and the second stage transistor of the nth stage is turned on such that the even gate1 signal of the nth stage has the first logic voltage due to the first logic voltage, and

wherein, during the third period, the first stage transistor of the nth stage is turned on and the second stage transistor of the nth stage is turned off such that the odd gate1 signal of the nth stage has the second logic voltage due to the even gate1 signal of the (n-1)th stage.

5. The display device of claim 1, wherein the display panel has first and second sides opposite to each other, and the gate driver includes first and second gate drivers at the first and second sides, respectively, of the display panel,

wherein the first gate driver includes the gate1 signal circuit, the odd gate2 signal circuit and the even gate2 signal circuit, and

wherein the second gate driver includes the emission signal circuit, the odd gate2 signal circuit and the even gate2 signal circuit.

6. The display device of claim 1, wherein the display panel includes a display area at a central portion thereof and a non-display area surrounding the display area,

wherein a plurality of pixels, a plurality of gate lines, a plurality of data lines, a plurality of vertical link lines and a plurality of horizontal link lines are disposed in the display area, and

wherein some of the plurality of data lines and some of the plurality of vertical link lines are connected to the data driver, others of the plurality of data lines are not connected to the data driver, and the plurality of horizontal link lines connect the some of the plurality of vertical link lines connected to the data driver and the others of the plurality of data lines not connected to the data driver.

7. The display device of claim 1, wherein the display panel includes a plurality of subpixels, and

wherein each of the plurality of subpixels comprises:

a storage capacitor connected to a first level voltage;  
 a first transistor switched according to a voltage of a first capacitor electrode of the storage capacitor;

a second transistor switched according to the gate2 signal and connected to the data signal and the first transistor;  
 a third transistor switched according to one of the even gate1 signal and the odd gate1 signal and connected to the storage capacitor and the first transistor;

a fourth transistor switched according to one of the even gate1 signal and the odd gate1 signal and connected to the storage capacitor and an initial voltage;

a fifth transistor switched according to the emission signal and connected to the first level voltage and the first transistor;

a sixth transistor switched according to the emission signal and connected to the first transistor;

a seventh transistor switched according to the gate2 signal and connected to an anode reset voltage; and

a light emitting diode connected between the sixth transistor and a second level voltage lower than the first level voltage.

8. The display device of claim 7, wherein the plurality of subpixels are disposed in an odd pixel line and an even pixel line of the display panel,

wherein the third and fourth transistors of the odd pixel line are switched according to the odd gate1 signal, and wherein the third and fourth transistors of the even pixel line are switched according to the even gate1 signal.

9. The display device of claim 7, wherein at least one of the first to seventh transistors is an oxide semiconductor thin film transistor. 5

10. The display device of claim 1, wherein the first and second stage transistors are disposed in one of the gate driver and the display panel. 10

11. The display device of claim 1, wherein in the even pixel line, a rising timing of the even gate2 signal coincides with a falling timing of the odd gate1 signal.

12. The display device of claim 8, wherein the odd and even pixel lines perform a sampling for a threshold voltage of the first transistor using the odd gate1 signal and the even gate1 signal, respectively. 15

13. The display device of claim 1, wherein the plurality of stages include a previous stage and a present stage, and wherein a gate electrode of the first stage transistor of the present stage is connected to an output terminal of the odd gate2 signal circuit of the present stage, a source electrode of the first stage transistor of the present stage is connected to an output terminal of the gate1 signal circuit of the previous stage, and a drain electrode of the first stage transistor of the present stage is connected to the odd pixel line of the display panel, respectively. 20 25

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